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				Application Number	10/735,110
				Filing Date	12/12/2003
				First Named Inventor	Nimmakayala et al.
				Group Art Unit	Unassigned
				Examiner Name	Unassigned
Sheet	3	of	4	Attorney Docket Number	P122/MII-94-69V18

OTHER PRIOR ART - NON PATENT LITERATURE DOCUMENTS				
Examiner Initials*	Cite No.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T ²	
LBT	C5	KRUG et al., "Fine Patterning of Thin Sol-Gel Films," Journal of Non-Crystalline Solids, 1992, pp. 447-450, vol. 147 & 148.		
	C6	Krauss et al., "Fabrication of Nanodevices Using Sub-25nm Imprint Lithography," Appl. Phys. Lett 67(21), 3114-3116, 1995		
	C7	CHOI et al., "Method and System of Automatic Fluid Dispensing for Imprint Lithography Processes," U.S. Patent Application Publication 2002/0094496. Published on July 18, 2002.		
	C8	CHOI et al., "Methods for High-Precision Gap and Orientation Sensing Between a Transparent Template and Substrate for Imprint Lithography," U.S. Patent Application Publication 2003/0093122. Published on July 18, 2002. 5/2003		
	C9	VOISIN, "Methods of Manufacturing a Lithography Template," U.S. Patent Application 10/136,188, Filed with USPTO on May 1, 2002.		
	C10	SREENIVASAN et al., "Step and Repeat Imprint Lithography Systems," U.S. Patent Application 10/194,414. Filed with USPTO July 11, 2002.		
	C11	SREENIVASAN et al., "Step and Repeat Imprint Lithography Processes," U.S. Patent Application 10/194,991. Filed with USPTO July 11, 2002.		
	C12	OTTO M. et al., "Step and Repeat UV-Nanoimprint Lithography: Material Issues," Nanoimprint and Nanoprint Technology Conference, San Francisco, December 11-13, 2002.		
	C13	JOHNSON, et al., "Advances in Step and Flash Imprint Lithography," SPIE Microlithography Conference, February 23-28, 2003.		
✓	C14	CHOI et al., "A Chucking System and Method for Modulating Shapes of Substrates," U.S. Patent Application 10/293,224. Filed with USPTO on November 13, 2002.		
LBT	C15	CHOI et al., "A Method For Modulating Shapes of Substrates," U.S. Patent Application 10/316,963. Filed with USPTO on December 11, 2002.		

Examiner Signature	/Leo B. Tentoni/	Date Considered	01/20/2007
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